

# Inclusion of Body-Bias Effect in SPICE Modeling of 4H-SiC Integrated Circuit Resistors

Philip G. Neudeck, NASA Glenn Research Center, Cleveland, OH USA, Neudeck@nasa.gov, <https://sic.grc.nasa.gov>

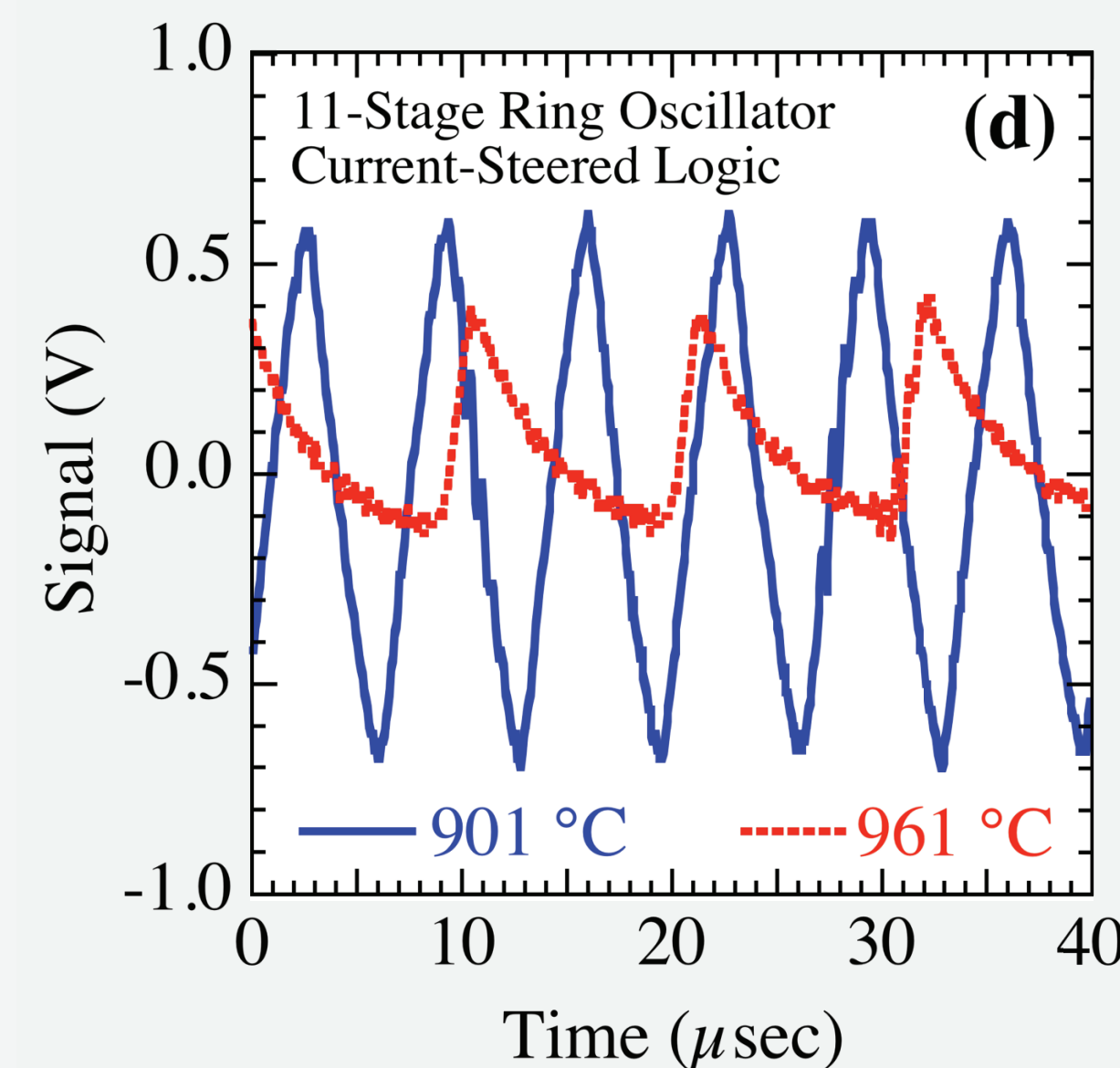
**Abstract.** The direct-current (DC) electrical behavior of n-type 4H-SiC resistors used for realizing 500 °C durable integrated circuits (ICs) is studied as a function of substrate bias and temperature. Improved fidelity electrical simulation is described using the SPICE NMOS model to simulate resistor substrate body-bias effect which is absent from the SPICE semiconductor resistor model.

## 1. Background

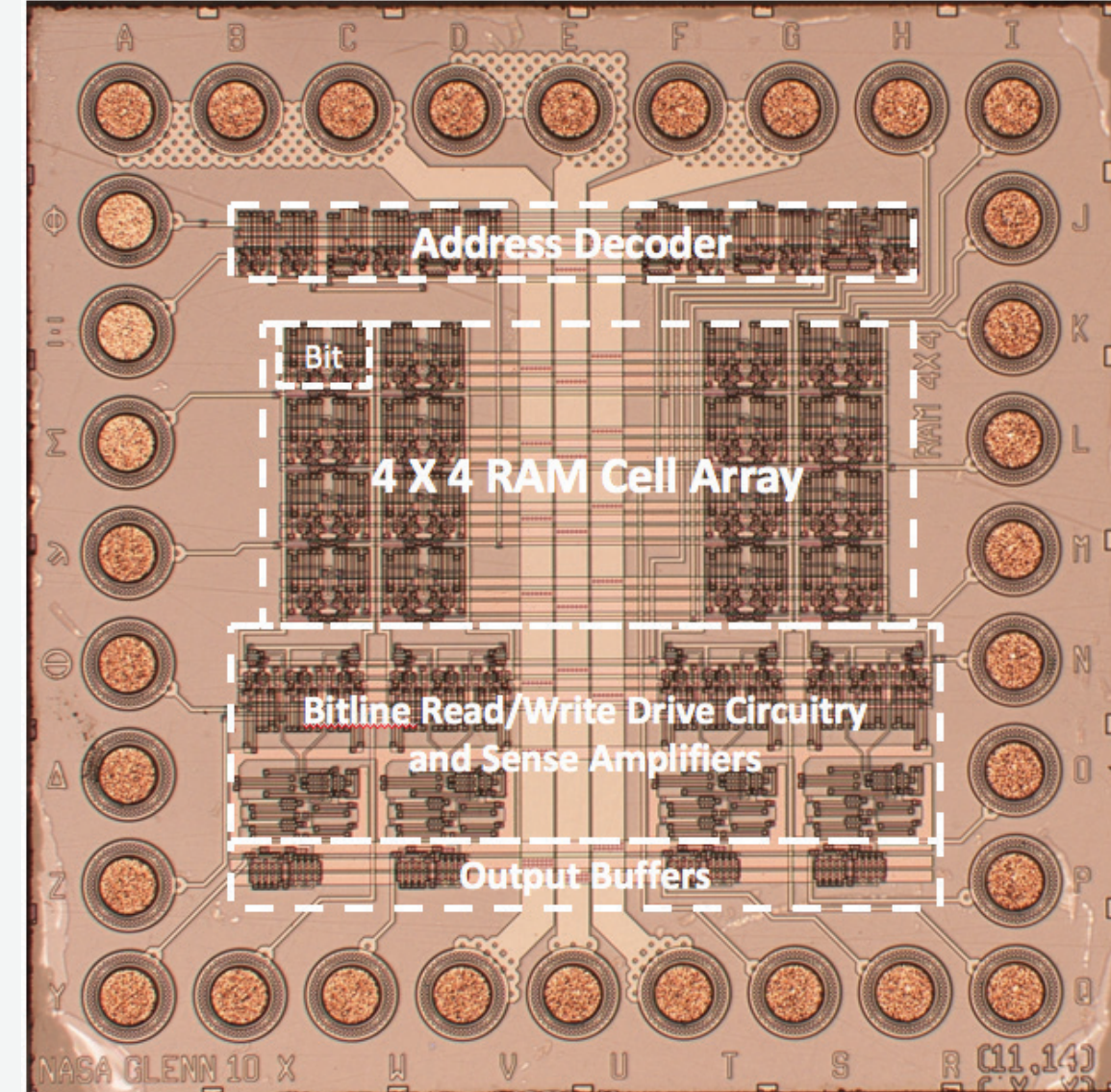
Increasingly capable extreme-temperature-durable 4H-SiC JFET ICs are being demonstrated.



**Fig. 1:** 3mm-by-3mm SiC JFET ring oscillator chip that operated for 3 weeks exposed to 460 °C 9.4 MPa caustic Venus surface atmospheric conditions [1].



**Fig. 2:** SiC JFET ring oscillator waveforms at record high temperature > 900 °C [2].

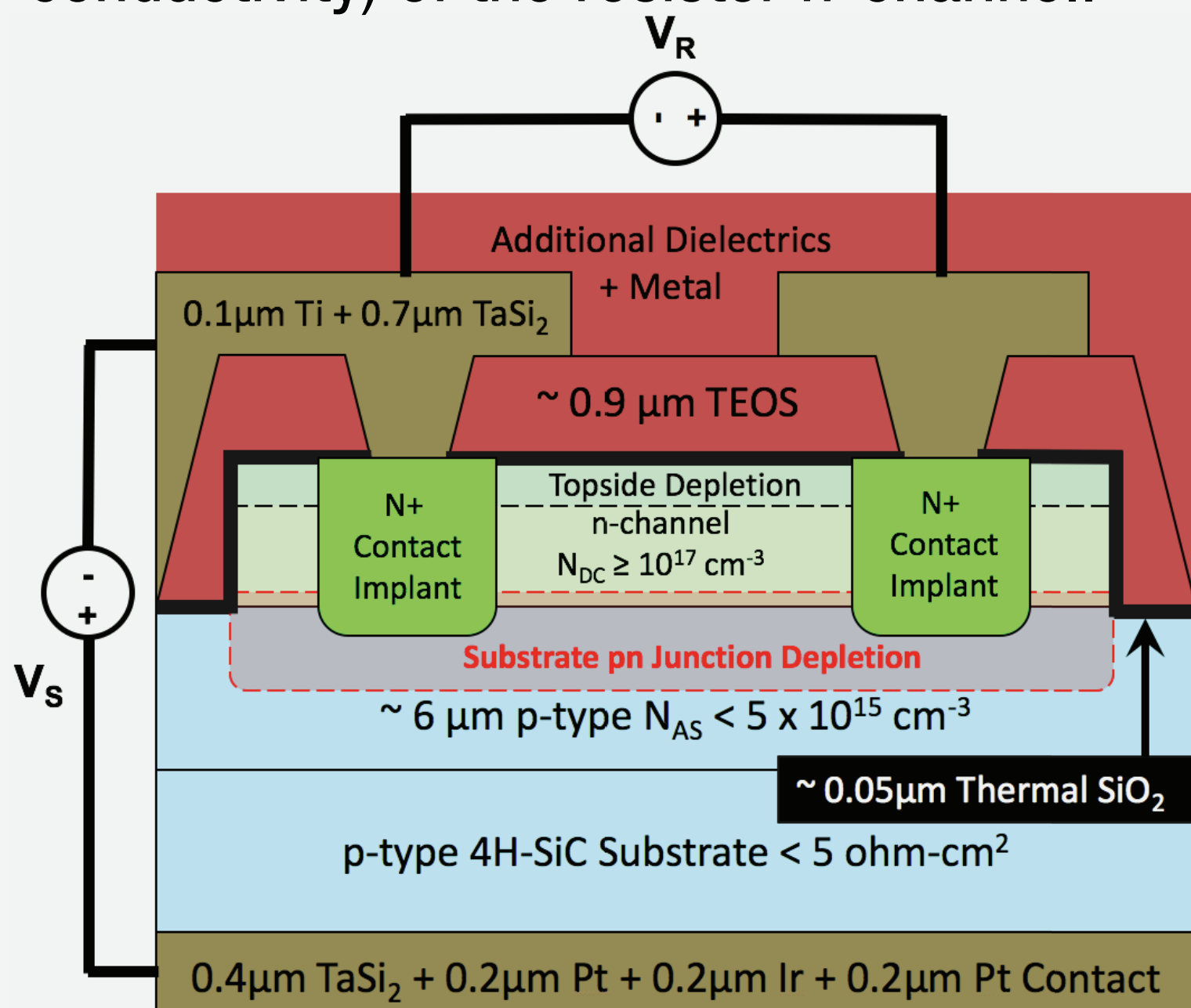


**Fig. 3:** 3mm-by-3mm SiC RAM chip (195 JFETs) operational for 5000+ hours at 500 °C [FR.D1.4 by D. Spry, Friday 9:30 AM].

Circuit engineers need SPICE models to design application-specific 4H-SiC JFET ICs.

## 2. Body-Bias Effect

As shown below in Fig. 4, the cross-sectional illustration of the SiC resistor structure used to realize the above JFET IC's, **bias-dependent substrate pn junction depletion** affects undepleted thickness (and therefore conductivity) of the resistor n-channel.

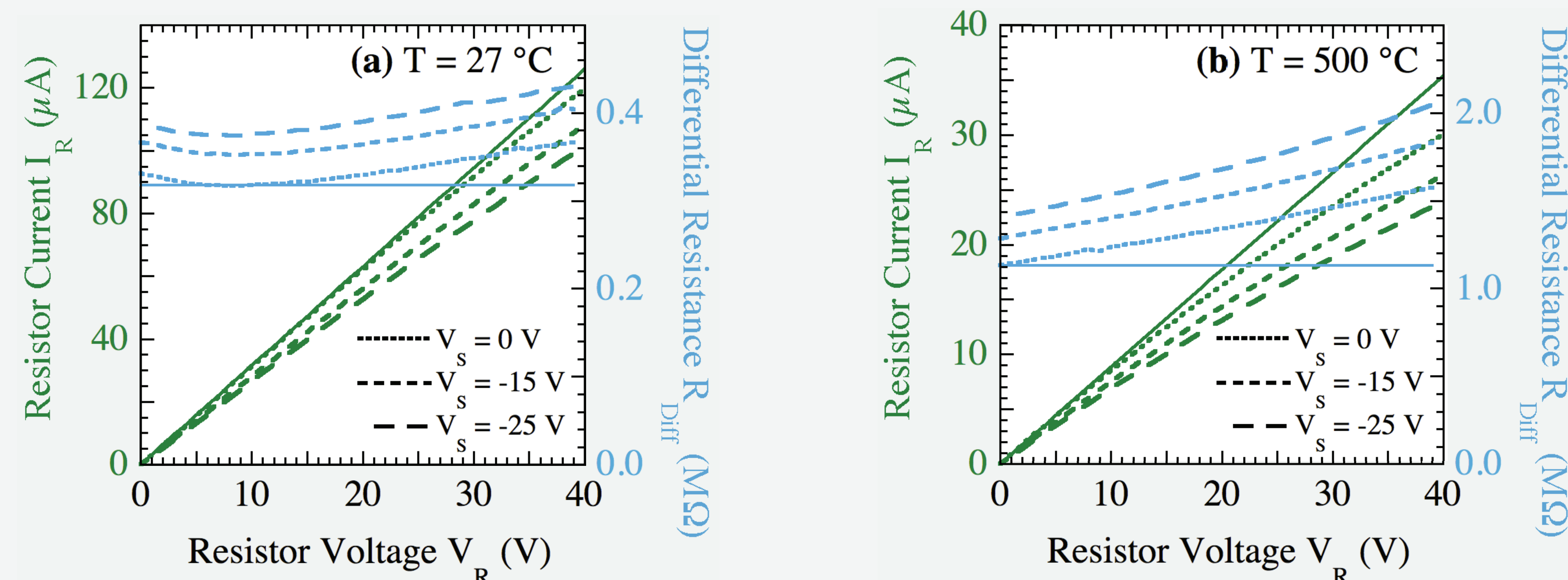


- Experimental SiC fabrication, packaging, and measurement setup are described in [2-5].
- For applied resistor bias  $V_R > 0$ , depletion widths change across the lateral length of the resistor.
- Current vs. voltage (I-V) characteristics and the IC resistor resistance value *depend on both  $V_R$  and  $V_S$* .

**Fig. 4:** Cross-sectional illustration of SiC resistor structure used in JFET IC's, including **substrate pn junction depletion** that gives rise to resistor body bias effect and applied substrate bias voltage  $V_S$  and resistor bias voltage  $V_R$ .

## 3. Measured Impact of Body Bias Effect on Resistor I-V Characteristics

- Body-bias effect causes mild non-linearity (i.e., downward bending) of resistor I-V characteristics (shown in green).
- Amount of non-linearity can be quantified by plotting differential resistance  $R_{diff} = dI/dV$  (shown in blue).



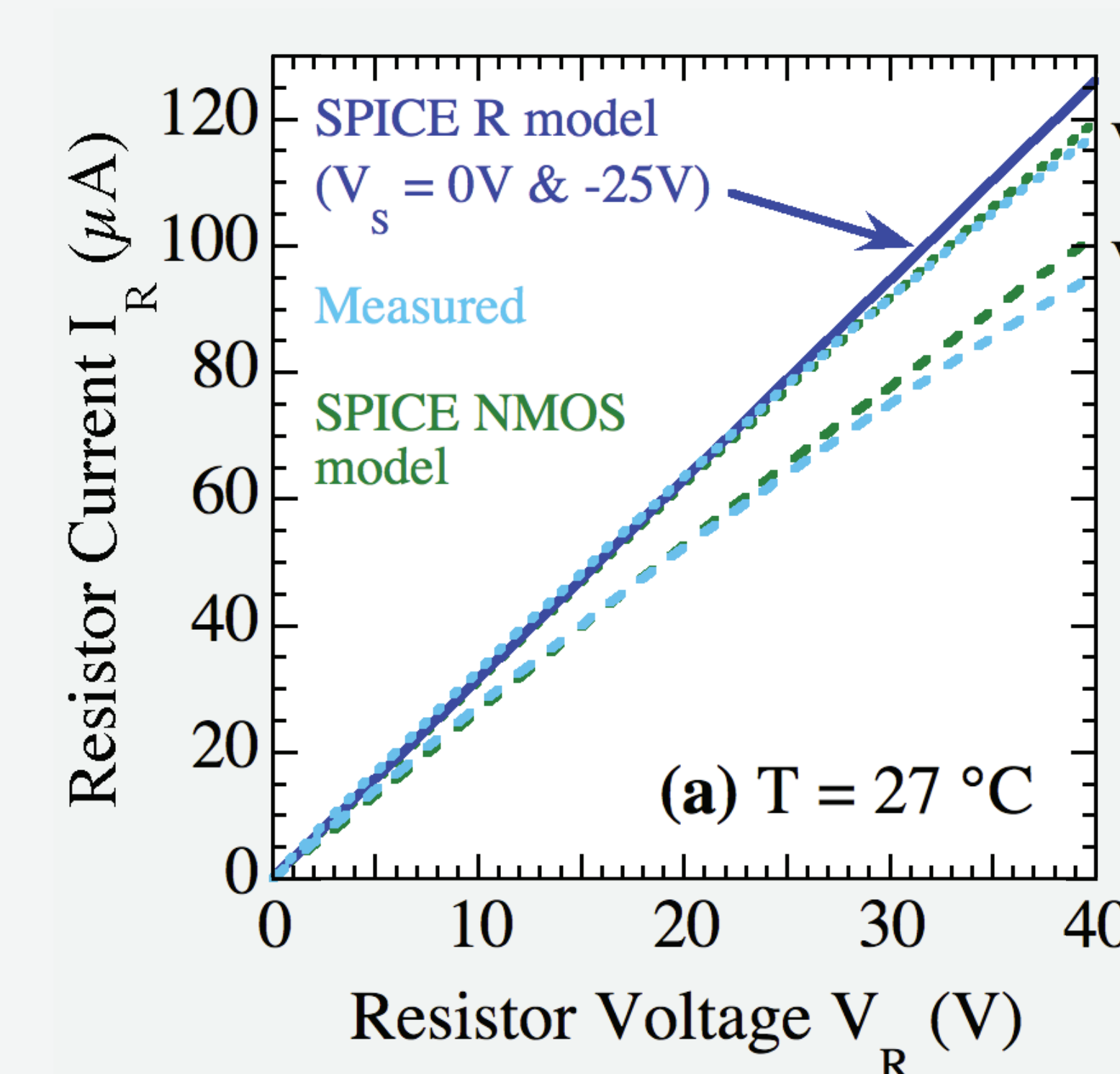
**Fig. 5:** Comparisons of DC-measured 80-square resistor I-V characteristics (dashed lines) with SPICE resistor model simulations (solid lines) at  $V_S$  of 0, -15, and -25 V at (a) 27 °C and (b) 500 °C.

- **Baseline SPICE resistor model (solid lines) [6] does not account for substrate body-bias effect, so it is incapable of modeling experimentally observed JFET IC resistors (and I-V characteristics) with high degree of accuracy.**
  - **Fails to model observed I-V bending/nonlinearity with increasing resistor bias  $V_R$ .**
  - **Fails to model observed dependence on substrate bias  $V_S$ .**
- Slightly rectifying metal contacts at 27 °C impacts  $R_{diff}$  for  $V_R < 15$  V.

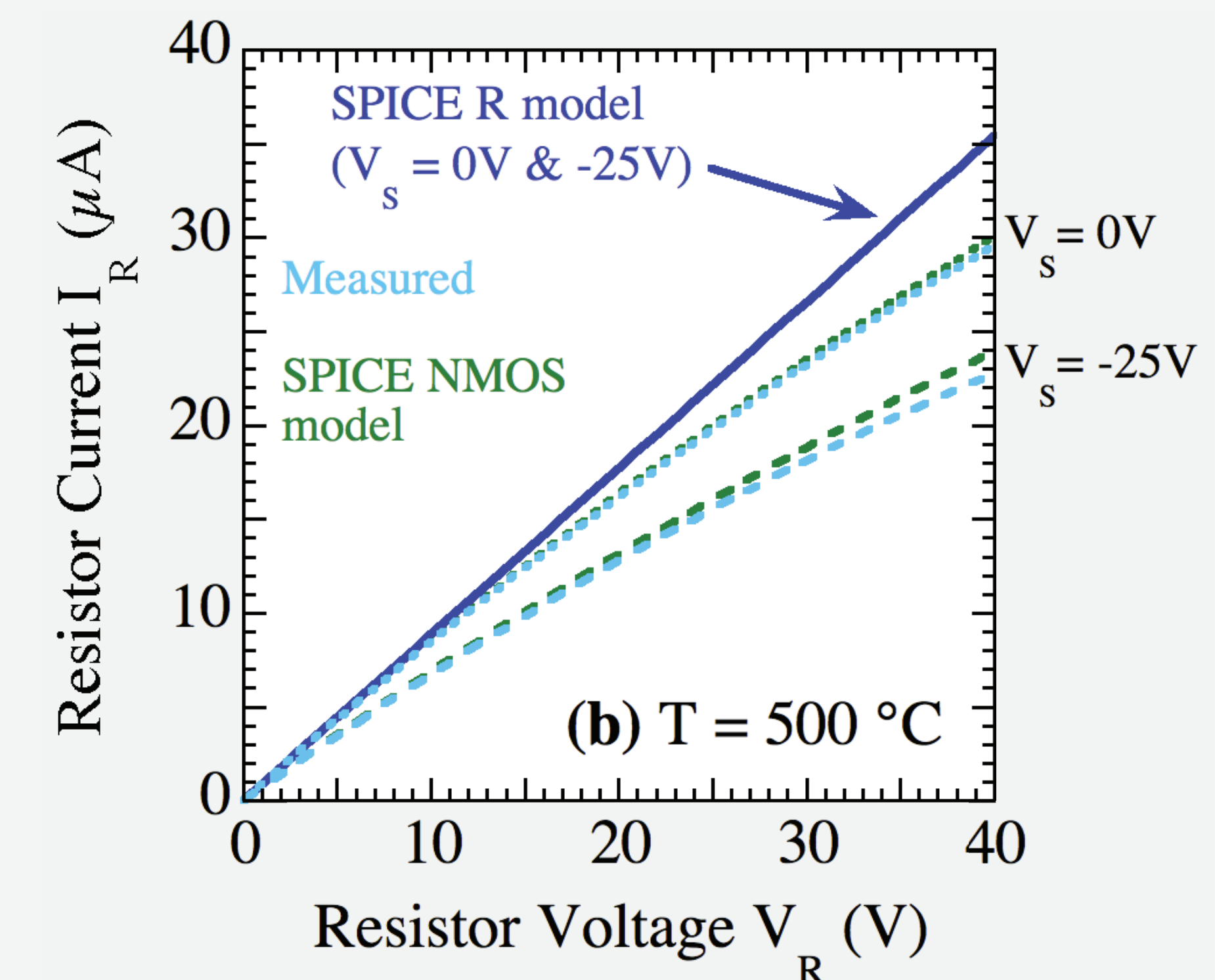
## 4. Resistor SPICE Model With Body Effect

While Fig. 4 depicts a SiC IC resistor cross section, this resistor structure can also be considered a long-channel JFET with the electrically biased p-epilayer/substrate serving as the gate terminal.

- The resistor can therefore be modeled using the SPICE NMOS LEVEL=1 model [6].
- The magnitude of negative substrate voltage  $V_S$  required to completely deplete the n-channel is large since  $NAS \ll NDC$  (Fig. 4), so the JFET operates in the linear region as a substrate-bias controlled resistor.
- The SPICE NMOS LEVEL=1 parameters for modeling IC resistors as N-MOSFETs with body bias effect (such as in green text SPICE listings shown below) can be extracted from Fig. 5 I-V data using the low drain-bias NMOS parameter extraction procedure described in [7].



```
*NASA Glenn SiC IC Resistor I-V Simulation 27C
V1 1 0
V2 2 0
MSICRES 1 2 0 2 sicresfet L=4.8E-4 W=6.0E-6
.MODEL sicresfet NMOS LEVEL=1 VTO=-155 KP=1.773E-6
CJ=6.856E-5 PB=2.87 RSH=0.0 PHI=1.435 GAMMA=0.0 JS=0.0
.DC v1 0 40.0 1.0 v2 0 -25.0 -25.0
.PRINT v(1) mag(i(v1))
.END
```



```
*NASA Glenn SiC IC Resistor I-V Simulation 500C
V1 1 0
V2 2 0
MSICRES 1 2 0 2 sicresfet L=4.8E-4 W=6.0E-6
.MODEL sicresfet NMOS LEVEL=1 VTO=-128 KP=5.474E-7
CJ=8.822E-5 PB=1.99 RSH=0.0 PHI=0.998 GAMMA=0.0 JS=0.0
.DC v1 0 40.0 1.0 v2 0 -25.0 -25.0
.PRINT v(1) mag(i(v1))
.END
```

**Fig. 6:** I-V comparison of linear R SPICE resistor model (solid dark blue) and NMOS SPICE body-effect resistor model (dashed green) with measured data (dashed light blue) for a 480-by-6μm resistor at (a) 27°C and (b) 500 °C. The SPICE decks for the NMOS model simulations are shown in green text below each plot.

**Substantially improved agreement with measured I-V is obtained using the NMOS SPICE model I-V compared with the SPICE R model I-V.**

## 5. Conclusion

For improved accuracy circuit design and modeling of 4H-SiC JFET ICs using SPICE, the NMOS resistor modeling approach described in this report should supercede/replace the standard SPICE R resistor model reported in [6], which ignores the body-bias effect.

## 6. Future Work

Comparison and design studies of SiC JFET integrated circuits using new SPICE NMOS resistor modeling.

## 7. Acknowledgements

D. Spry, L. Chen, G. Beheim, N. Prokop, M. Krasowski, K. Moses, J. Gonzalez, M. Mrdenovich, R. Buttler, R. Meredith, D. Lukco, C. Chang, G. Hunter, G. Ponchak, L. Matus. Work funded jointly by NASA Aeronautics (Transformative Tools and Technologies project) and Science Mission (Planetary Instrument Concepts for the Advancement of Solar System Observations project) Directorates.

## 8. References

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